

10/568126

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PATENT

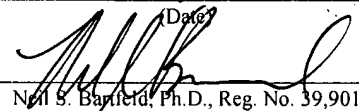
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Masuda et al.
Appl. No. : Unknown (U.S. National Phase of
PCT/JP2004/012235)
Filed : Herewith
For : POSITIVE PHOTORESIST
COMPOSITION AND RESIST
PATTERN FORMATION
Examiner : Unassigned
Group Art Unit : Unknown

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all
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February 14, 2006


Neil S. Bartfield, Ph.D., Reg. No. 39,901

PRELIMINARY AMENDMENT

Mail Stop PCT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination of the above-referenced application, please enter the following
amendments.

Amendments to the Specification begin on page 2 of this paper.

Remarks begin on page 3 of this paper.